

**AMENDMENTS TO THE SPECIFICATION**

Please replace paragraph beginning on page 8, line 1 with the following amended paragraph:

Referring to Fig. 4c, subsidiary switch source and drain electrodes 133a and 133b made of a non-transparent metal are formed on the switch source and drain electrodes 129a and 129b while contacting the exposed portions “ $\Delta L$ ” of the ohmic contact layers 125a and 125b, respectively. Thus, the switch drain and source electrodes have a dual layered structure. As shown in Fig. 4c, the non-transparent metal layer of the dual layered drain electrode of the switch TFT extends over the transparent conductive material layer and contacts the ohmic contact layer. In addition, the extended edge of the non-transparent metal layer of the dual layered drain electrode of the switch TFT substantially coincides with one of the edges of the ohmic contact layer. The non-transparent metal is selected from the group consisting of tungsten, molybdenum and chrome, each of which has a lower contact resistance than the transparent conducting material such as indium tin oxide.